

Notice of References Cited	Application/Control No. 10/725,139		Applicant(s)/Patent Under Reexamination SATO ET AL.	
	Examiner Elias Desta		Art Unit 2857	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2003/0038112	02-2003	Liu et al.	216/60
*	B	US-2005/0011611	01-2005	Mahoney et al.	156/345.24
*	C	US-2005/0199341	09-2005	Delp et al.	156/345.24
	D	US-			
	E	US-			
	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

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	N					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Babiker et al., 'Complete Monte Carlo RF Analysis of "Real" Short-Channel Compound FET's', August 1998, IEEE Publication, Vol. 45, No. 8, pages 1644-1652
	V	Coumou, 'Advanced RF Metrology for Plasma Process Control', October 2003, MKS Instruments, pages 1-5
	W	Khargonekar et al., 'Intelligent Electronics Manufacturing: Modeling and Control of Plasma Processing', August 1998, UOM Publication, pages 1-57
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.